



Single mask technology implementation

Piotr Bielówka

Single mask technology implementation

a) New machinery:

Old Kapton etching machine



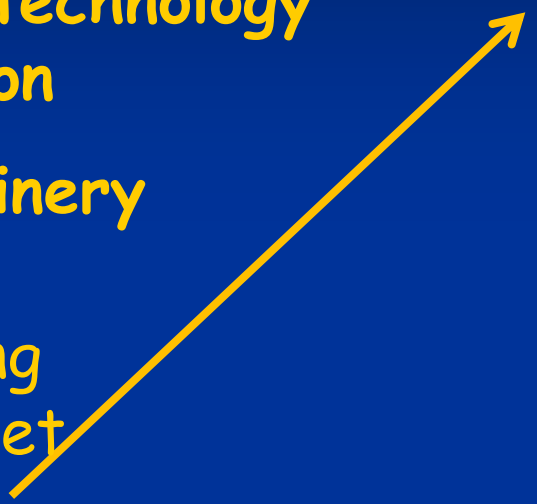
New Kapton etching machine

10th RD51 Stony Brook

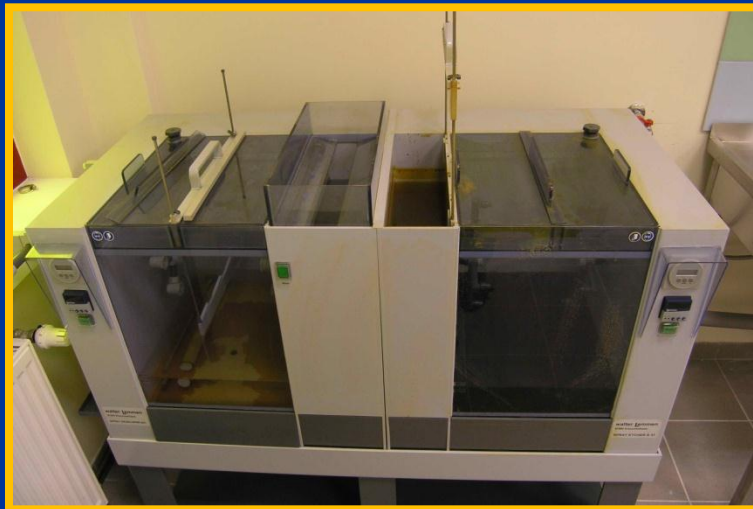
Single mask technology
implementation

a) New machinery

Old developing
and etching set



New developer



New Cu etcher

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Single mask technology implementation

a) New machinery



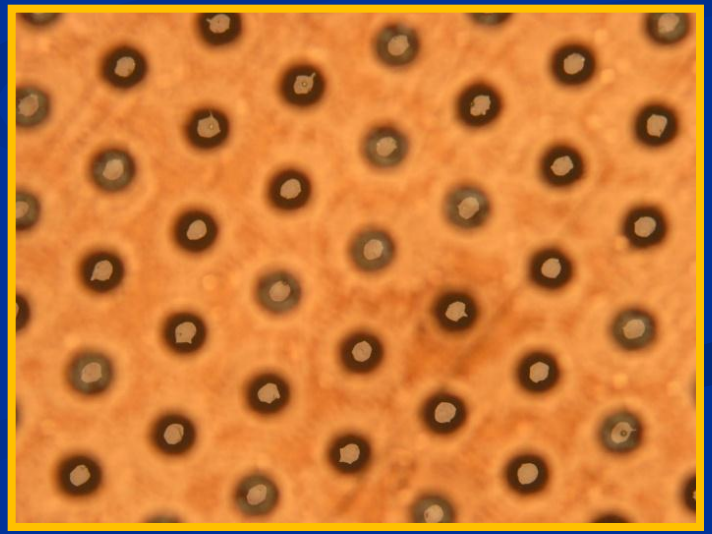
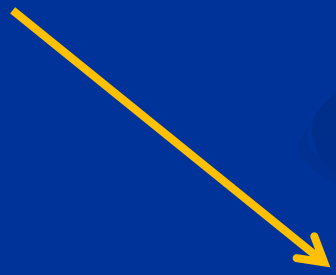
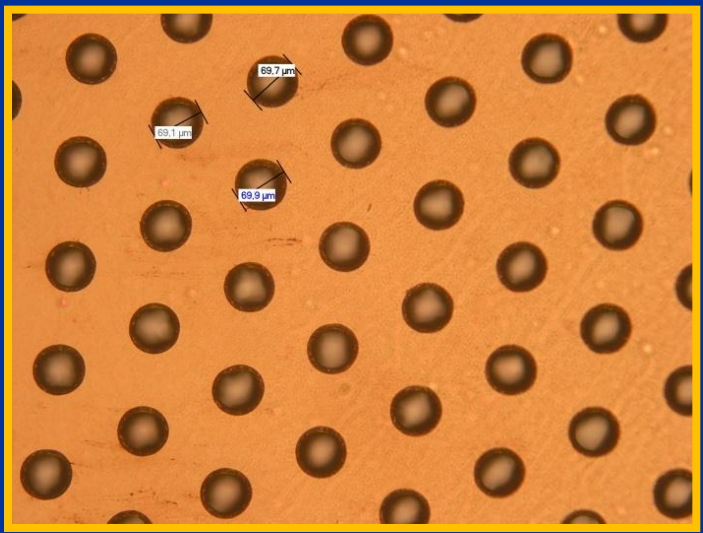
Additional optic microscope.



Current optic microscopes set.

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b) Preliminary „Single side“ Kapton etching test :



Problems caused by:

- Cleaning procedure
- High etching reagents concentration



Single mask technology implementation

Plans for future:

- Implementing a new set of PCB machines, dedicated to single mask GEM technology - beginning of 2013.
- Automatization of electrical testing position
- Testing, tuning, work - until production starts